

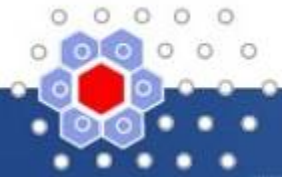
MONA

Merging Optics & Nanotechnologies

Applications and Markets

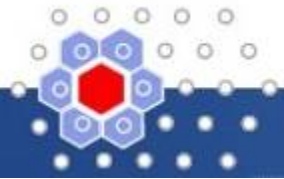
Krassimir Krastev and Eric Mounier
Optics Valley & Yole Développement

First MONA workshop, April 7th 2006, Strasbourg

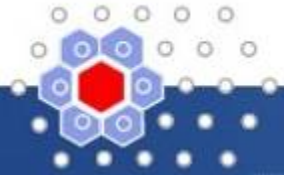


- ◆ **Materials and Applications**
 - Describe your applications
 - What are in your view the limitations and bottlenecks in 5-10 coming years in your area?
 - In your view, could nanophotonics and nanotechnologies overcome some of these limitations.
 - In which type of field/product/technology/industry are you seeing a development of the use of nanotechnologies in your area/domain?
 - Do you already use nanophotonics concepts/nanomaterials in your devices/applications ?
 - What do you expect from the use of nanoscale materials: new functions, lower cost, higher performance/integration
- ◆ **Equipment and Processes**
 - In your view, are nanomaterials or/and nanophotonic related fabrication processes compatible with current processes and equipment?
 - In your view, what are the main difficulties for the fabrication of nanophotonic devices current equipment?
 - Is there any need for the development of any new equipment?
- ◆ **European Context**
 - In your view what are the strength/weakness of the European industry in the area of nanophotonics and nanotechnologies and what are the possible directions of improvement

→ 15 filled questionnaires received



- ◆ Optical Interconnects
- ◆ Datacoms/Telecoms
- ◆ Lighting/Displays
- ◆ Data Storage
- ◆ Image sensors
- ◆ Photovoltaics



Box-to-box interconnects (> 10 m): optical fiber

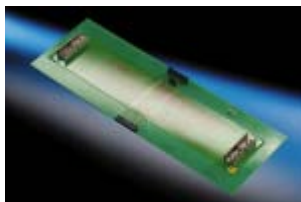
Used today



Board-to-board interconnects (1 -10 m); backplanes are potential applications for optical interconnects as bandwidth is increasing

Many technologies have been used (polymer WG, fiber ribbon with VCSELs ...): **only niche market today (aeronautics)**

> 2006 (current developments for datacom, switches ... FCI)



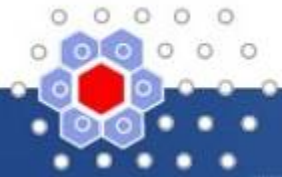
Chip-to-chip interconnects (1 - 10s cm): density of Cu traces on FR4 is constrained by EMI and crosstalk problems. Solutions have been tested but unsuitable for mass production. Polymer strips and VCSELs have been demonstrated (Intel)

2010

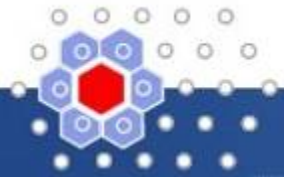


On-chip interconnects (< 1 cm): from Al to Cu interconnect to photonic ? CMOS-compatible materials: Si, SiO₂, Si₃N₄ and SiO_xN_y could be used as waveguides and cladding.

2010 - 2015



- ◆ **Objective is to have a high level of integration**
- ◆ **This is today a niche market for board-to-board (aeronautics)**
 - Market is planned to take off in 2012 for chip-to-chip @ 22 nm node (but will price be competitive?)
- ◆ **Bottlenecks in 5-10 years:**
 - Propagation performance limitations: signal propagation delay time, power consumption, bandwidth
 - Cu metallization (electro-migration)
- ◆ **Nanophotonics should answer to higher performance of signal propagation and Ultra Large System Integration (ULSI)**
 - Issues are: coupling/decoupling light, alignment precision, temperature resistance
...
- ◆ **Nanophotonics is only a concept for this application so far**
- ◆ **Compatibility w/ existing equipments and processes are highly desirable.**
- ◆ **European context: limited support from applied R&D and industry**



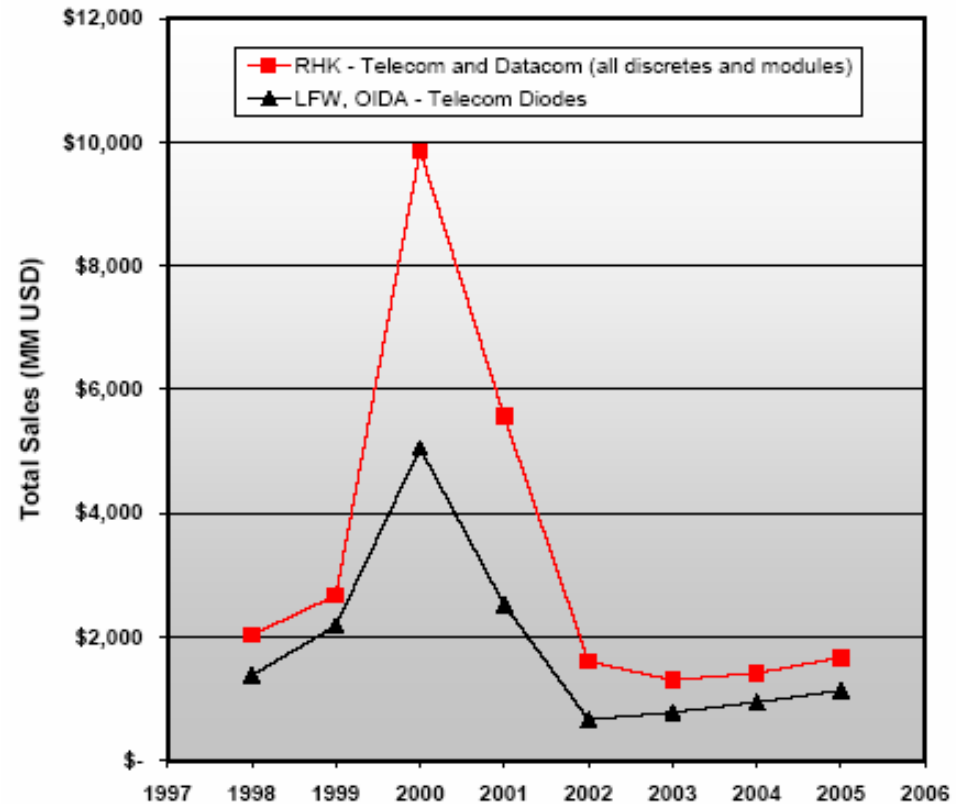
“TAM for all photonics components in the communications (telecom/datacom) industry: \$2B USD in 2003 and \$2.5B USD in 2004.

\$10.7B USD in 2000!

This aftermath of the internet bubble burst resulted in anywhere from a 4x to a 10x reduction in the TAM, and is just now growing back to late-1990's level market sizing .”

(MIT source)

First MONA workshop, April 7th 2006, Strasbourg



Annual sales for discrete photonic components and modules, and for telecom lasers.



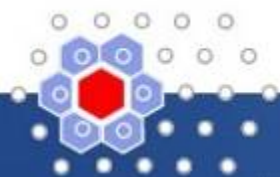
- Limitations and bottlenecks in 5-10 coming years
 - InP processing

- Could nanophotonics and nanotechnologies overcome some of these limitations.
 - Moving further down the nano route blurs the boundaries between semiconductor materials, allowing synthetic bandgaps and wavelength scale beam manipulation.

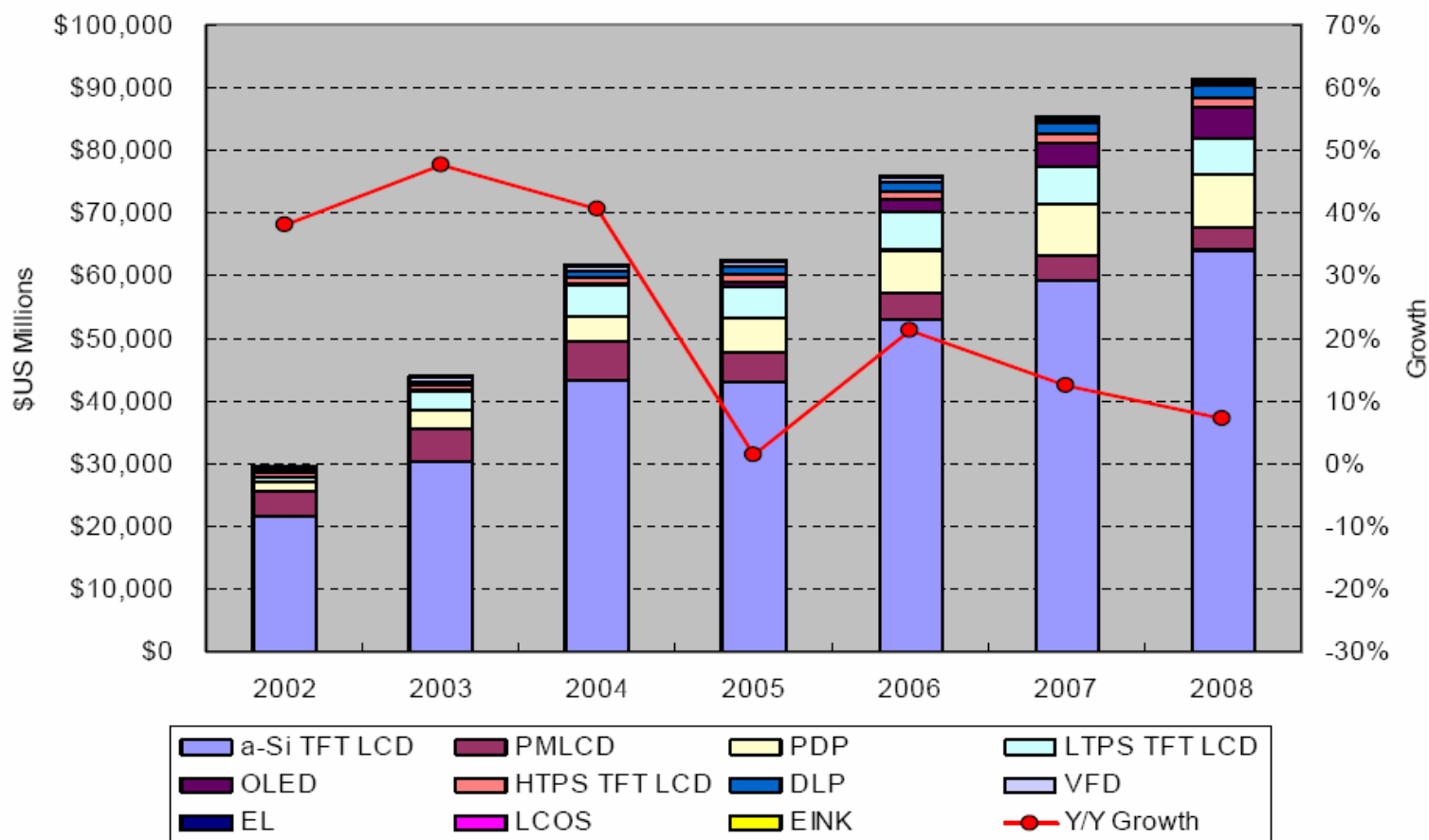
 - The field of PBGs (Photonic Band Gap) will have impact on wavelength/subwavelength scale beam manipulation/ switching

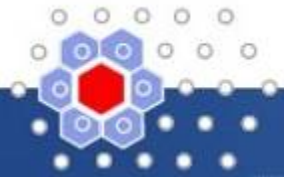
 - It moves away from the macro scale devices such as AWGs.
 - PGB is key enabler for future high level integration, potentially 3D.

 - Industrial laser design – a key driver is maximising power without too much compromise to brightness so integration methods for array beamforming, mutiwavelength beam combining etc... will be very important.
 - nano technologies such as QD's should help drive fundamental efficiency in industrial lasers – reducing heat, simplifying cooling, overall driving better conversion efficiency and versatility



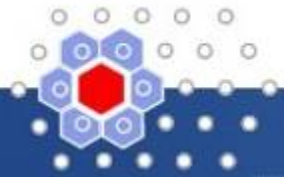
- ◆ Total display revenues are forecast to grow from \$59.3 B in 2003 to \$103.9B by 2008 (CRT + FPDs)



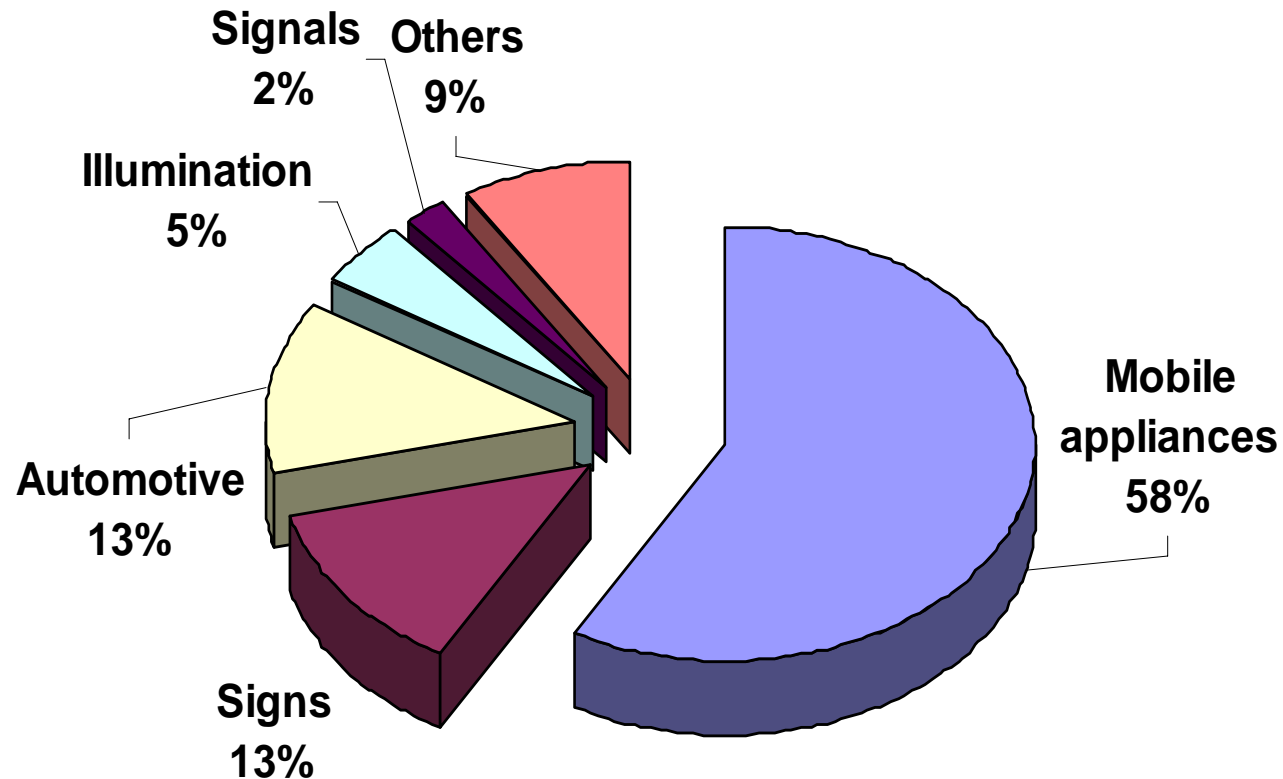


- ◆ Technical requirements
 - Low thickness
 - Low weight
 - Low power consumption (back-lighting)
 - High contrast (1000:1)
 - Fast response time (in the order of μs)
- ◆ Visual comfort
 - Wide viewing angles
 - New design flexibility (wide range of sizes, flexible ...)
- ◆ Product lifetime
 - Non-decreasing performances over lifetime
 - Long lifetime (10 years)
 - Good resistance to environmental conditions (temperature, moisture, shocks ...)
- ◆ Nanotechnology could bring CNT instead of μtips :
 - fully compatible fabrication process for large area
 - low cost
 - Low power consumption
- ◆ Conventional FEDs are limited to small display
- ◆ But no industrial scale fabrication equipment today for CNT.





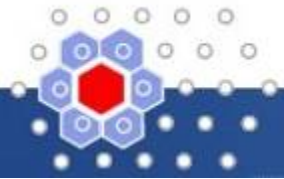
Lighting: LED applications breakdown (All colors, all materials, 2004)



Sources: Strategies unlimited



New markets are emerging today for LEDs & HBLEDs such as portable projection



- ◆ Current bottlenecks:
 - Quantum efficiency
 - Light extraction
 - Cooling
 - Packaging
 - Color steering
 - Cost/lumen/W

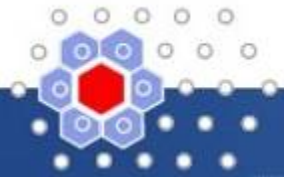
- ◆ Nanophotonics could overcome the above limitations: Photonic Crystals for efficiency and CNT for cooling.

- ◆ Nanophotonics concepts such as Quantum Wells are under investigation.

- ◆ Using nanoscale materials will improve device characteristics (efficiency, cooling, light extraction) as well as integration
 - Price will be important for market penetration

- ◆ Current equipment is not suitable for realizing nanostructures because high precision is needed:

- ◆ European industry tends to be a follower instead of an innovator

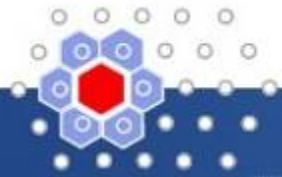


- ◆ In the 5-10 years to come, bottlenecks are:
 - High efficiency, long lived blue emitting materials, high throughput process, water protection, light distribution control, low cost substrates, large area

- ◆ Nanotechnologies could enable:
 - Better light control
 - Low cost substrates
 - Barrier coatings

- ◆ Need for equipments able to process large area with high throughput

- ◆ The European context:
 - Excellent academic support, strong innovation, broad expertise
 - Lack of coordinated vision, limited risk taking, limited cooperation between different value chains

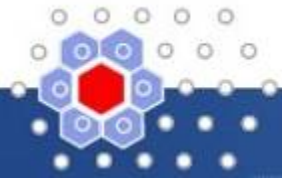


Global Magnetic and Optical Data Storage Market (\$ Billions)

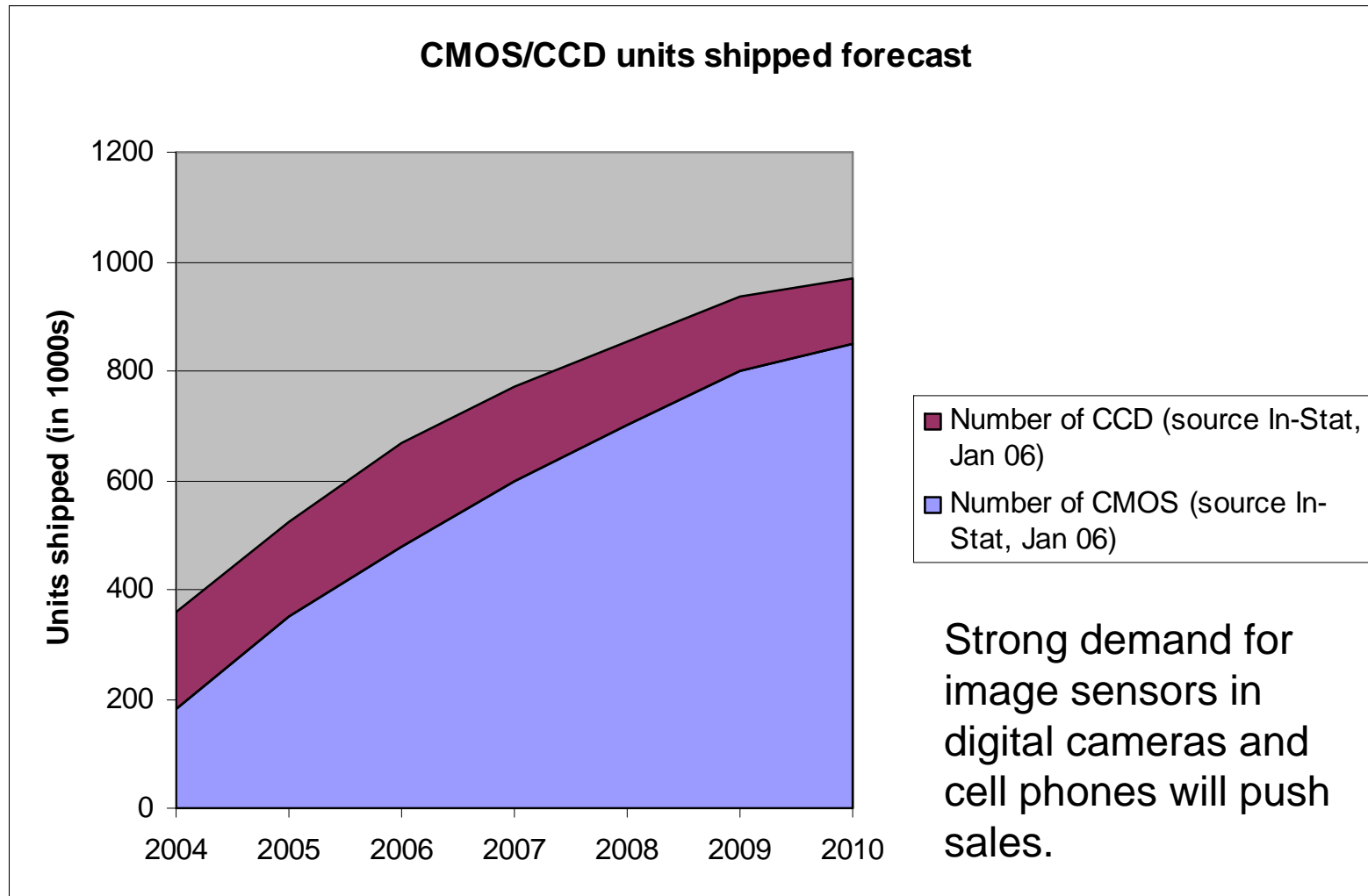
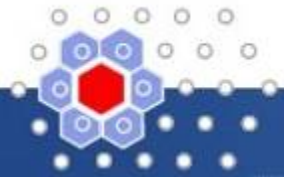
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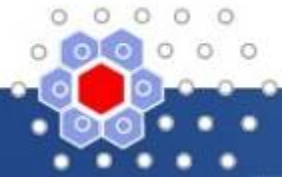
	2005	2010	AAGR% 2005-2010
Magnetic Media (including hard drive heads)	7.4	9.3	4.8
Optical Media	12.4	30.6	19.8
Total	19.8	39.9	15.1

- > 60% of the data storage market shares were held by optical storage media in 2005 and this part is expected to increase to 77% in 2010.
- Emerging optical media (blu-ray and HD-DVD, holographic and near-field storage) are not significant today but are expected to reach 4% market shares in 2010.

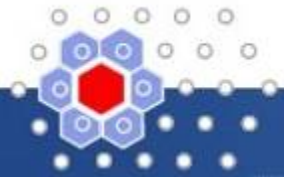


- ◆ Technical requirements
 - To overcome the physical limit (paramagnetic limit) which is 150 Gbit/in² which could be reached in 2010
 - Product lifetime: no data erased over the time
- ◆ Competing technologies:
 - Blue LDs, nano-mechanical storage (IBM) ...
 - Philips should launch Blu-Ray disc in 2006
 - Flash RAM technology could gain important market share in data storage

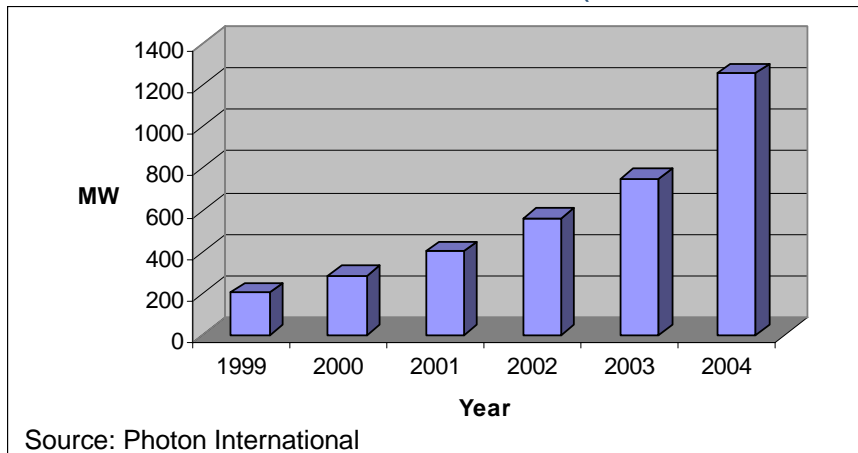




- ◆ Markets targeted are for very small optical products (mobile phones imaging, medical products)
- ◆ Limitations and bottlenecks in 5 – 10 coming years:
 - Pixel size (in the 1.5 μm range)
 - High performance classical lenses
 - Accurate mechanical assembly
 - Materials for pixel-sized colour filters
 - On chip image & signal processing
 - Wafer integration of optical functions
- ◆ Nanophotonics could allow on-chip integration
- ◆ Nanophotonic could bring combination of CMOS process w/ optimized sensitive thin layers and above IC detection.
 - Compatibility with current manufacturing processes is a MUST.
 - No compatibility so far.
- ◆ R&D on nanomaterials has started already for filtering
- ◆ Benefits from nanoscale materials:
 - Higher pixel density > denser chip integration > lower size > lower cost > larger use.
 - New functions integration on/off chip
- ◆ Nanomaterials processing is mostly not compatible with current equipments
- ◆ At the European level, more coordination between “photonics” research and other R&D sectors (such as semiconductors) is needed.



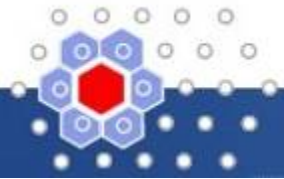
- World PV market evolution (what has been sold)



- ✓ The production has increased by more than 60% in 2004.
- ✓ Since 1980, it is growing by 25% per year.

- Technology market share in 2004 (conversion photon → energy):

- Mono-crystalline Si 36%
- Multi-crystalline Si 54%
- a-Si 4.4% → First turn-key plant ready in 2006 from Unaxis
- Ribbon Si 3.3% → Evergreen and Schott Solar are building new plants
- CIS/CIGS 0.4% → Several pilot plants running, 15 MW and 27MW plants under construction
(CopperIndiumGalliumSelenium)
- CdTe 1.1% → First Solar is already mass-producing and expanding production capacity



- ◆ **Challenges**
 - Stability
 - Lifetime
 - Large area processing
 - Efficiency
 - Reducing cost by reducing silicon wafer thickness < 200 μ m (Si wafer represents about 40% of the module cost)
 - Improving the factory yield and throughput

- ◆ **Organic PV could overcome some of these limitations: large interface areas with nanostructured surfaces (higher performance, higher integration)**
 - C60 is already used